



- Drafts
 - BRS:
 - Pending
 - Active
 - L1: (9) ((electron near2 beam) and gun and primary and (
 - L2: (1) ((electron near2 beam) and gun and primary and (
 - L3: (1) ((electron near2 beam) and gun and cathode and
 - L4: (0) ((electron near2 beam) and gun and primary and (
 - Failed
 - Saved
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DBs US-PGPUB

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|---|------|-----|------|---|----------|---------------------|----------|----|-------|
| 1 | BRS | L1 | 9 | ((electron near2 beam) and gun and primary and (sample or object or material or semiconductor) and separatS3 and secondary and lens and acceleratS3 and (optical near2 system) and detector and deflectS3 and scanning).clm. | US-PGPUB | 2006/11/22 10:24 | | | |
| 2 | BRS | L2 | 1 | ((electron near2 beam) and gun and primary and (sample or object or material or semiconductor) and separatS3 and secondary and lens and acceleratS3 and (optical near2 system) and detector and deflectS3 and memorS3 and switchS3 and CPU and (image near2 processS3)).clm. | US-PGPUB | 2006/11/22 10:21 | | | |
| 3 | BRS | L3 | 1 | ((electron near2 beam) and gun and cathode and wehnelt and electrode and anode and (multiemitter or (multi adj emitter)) and heatS3 and (adjustS4 near2 mechanism) and direction and tilt and perpendicular and plane).clm. | US-PGPUB | 2006/11/22 10:23 | | | |
| 4 | BRS | L4 | 0 | ((electron near2 beam) and gun and primary and (sample or object or material or semiconductor) and separatS3 and secondary and lens and acceleratS3 and (optical near2 system) and guidS3 and director and demagnification and image and detector and (multiaperture or (multi adj aperture))).clm. | US-PGPUB | 2006/11/22 10:27 | | | |

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FAST - [Interference_Search_History_11051602.wspc1]

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☐ Failed
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((electron near2 beam) and gun and primary and (sample or object or material or semiconductor) and separatS3 and secondary and lens and acceleratS3 and (optical near2 system) and detector and deflectS3 and scanning).chn.

BRS form IS&R form Image Text HTML

| | U | 1 | Document ID | Issue Date | Pages | Title | Current OR | Current XRef | Inventor |
|---|--------------------------|--------------------------|-------------------|------------|-------|---|------------|---------------------|--------------------------|
| 1 | <input type="checkbox"/> | <input type="checkbox"/> | US 20060243906 A1 | 20061102 | 24 | Inspection method and inspection system using charged particle beam | 250/307 | | Fukada; Atsuko et al. |
| 2 | <input type="checkbox"/> | <input type="checkbox"/> | US 20060097200 A1 | 20060511 | 29 | Electron beam apparatus and a device manufacturing method by using said electron beam apparatus | 250/493.1 | | Nakasuji; Mamoru et al. |
| 3 | <input type="checkbox"/> | <input type="checkbox"/> | US 20050263715 A1 | 20051201 | 57 | Objective lens, electron beam system and method of inspecting defect | 250/396ML | 250/310; 250/311 | Nakasuji; Mamoru et al. |
| 4 | <input type="checkbox"/> | <input type="checkbox"/> | US 20050133733 A1 | 20050623 | 29 | Electron beam system and method of manufacturing devices using the system | 250/492.1 | | Nakasuji; Mamoru et al. |
| 5 | <input type="checkbox"/> | <input type="checkbox"/> | US 20040135515 A1 | 20040715 | 22 | Electron beam apparatus and device manufacturing method using same | 315/5.41 | 315/14 | Hamashima; Muneki et al. |
| 6 | <input type="checkbox"/> | <input type="checkbox"/> | US 20040119023 A1 | 20040624 | 29 | Electron beam apparatus and a device manufacturing method by using said electron beam apparatus | 250/396R | | Nakasuji; Mamoru et al. |
| 7 | <input type="checkbox"/> | <input type="checkbox"/> | US 20030155509 A1 | 20030821 | 29 | Electron beam system and method of manufacturing devices using the system | 250/310 | | Nakasuji; Mamoru et al. |
| 8 | <input type="checkbox"/> | <input type="checkbox"/> | US 20020148961 A1 | 20021017 | 104 | Electron beam apparatus and device production method using the electron beam apparatus | 250/311 | | Nakasuji; Mamoru et al. |
| 9 | <input type="checkbox"/> | <input type="checkbox"/> | US 20020142496 A1 | 20021003 | 83 | Electron beam apparatus and method of manufacturing semiconductor device using the apparatus | 438/14 | 250/492.3 | Nakasuji; Mamoru et al. |

LAST - [Updated_EAST_Class_10697647.wspc1]

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DBs US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB

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BRS:
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L6: (2675) (electron near2 beam) and deflectS3 and g
L7: (2645) 6 and (sample or object or semiconductor
L8: (21) 7 and (313/409 or 313/413 or 313/421)
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Favorites
Tagged (0)
UDC
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| | Type | L # | Hits | Search Text | DBs | Time Stamp | Comments | Er | Erro |
|---|------|-----|------|---|--|------------------|----------|----|------|
| 1 | BRS | L6 | 2675 | (electron near2 beam) and deflectS3 and gun and lens and separatS3 and detectS3 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | 2006/11/22 10:30 | | | |
| 2 | BRS | L7 | 2645 | 6 and (sample or object or semiconductor or wafer or material) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | 2006/11/22 10:31 | | | |
| 3 | BRS | L8 | 21 | 7 and (313/409 or 313/413 or 313/421) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | 2006/11/22 10:32 | | | |